

AF/EPW

UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applicant:

Robert P. Meagley et al.

Serial No.: 10/688,521

Filed: October 17, 2003

For: Reducing Photoresist Line Edge
Roughness Using Chemically-
Assisted Reflow

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Art Unit: 1752

Examiner: Amanda C. Walke

Docket: ITL.1026US
P16713

Assignee: Intel Corporation

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

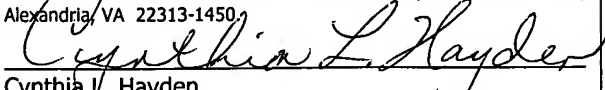
REPLY TO FINAL REJECTION

Sir:

In response to the final rejection mailed August 26, 2005, reconsideration is requested in view of the following remarks.

Date of Deposit: September 19, 2005

I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.


Cynthia L. Hayden